

Supplementary information

Preferential Zinc Sputtering During Growth of Aluminum Doped Zinc Oxide Thin Films by Radio Frequency Magnetron Sputtering

Kion Norrman, Poul Norby and Eugen Stamate

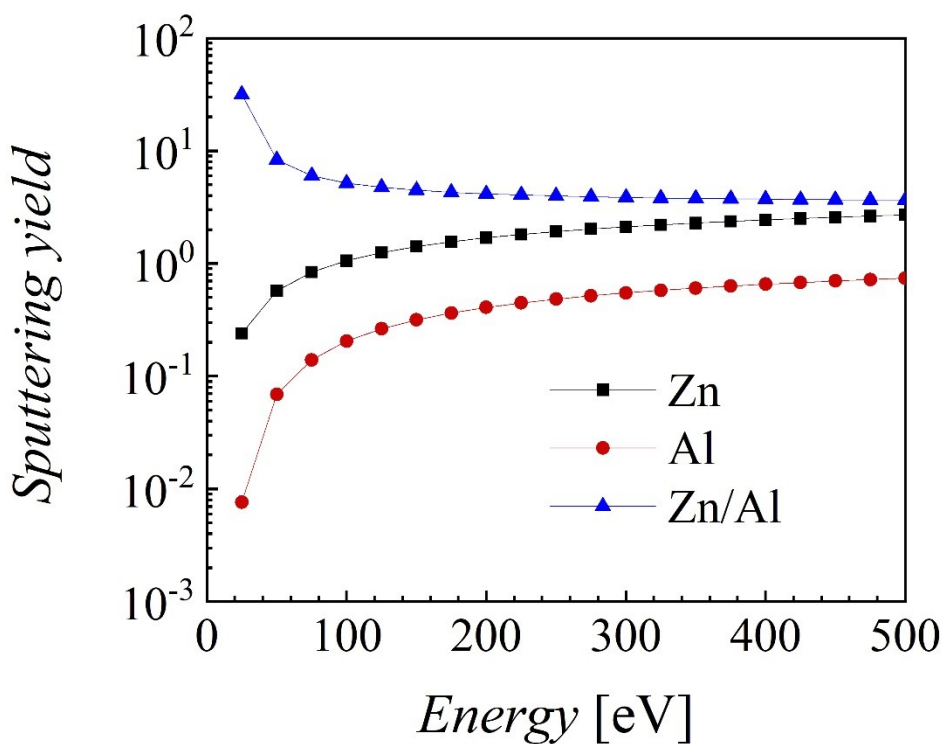


Fig. S1 Sputtering yield on Zn and Al targets (including the Zn/Al ratio) as a function of incident oxygen ion energy.

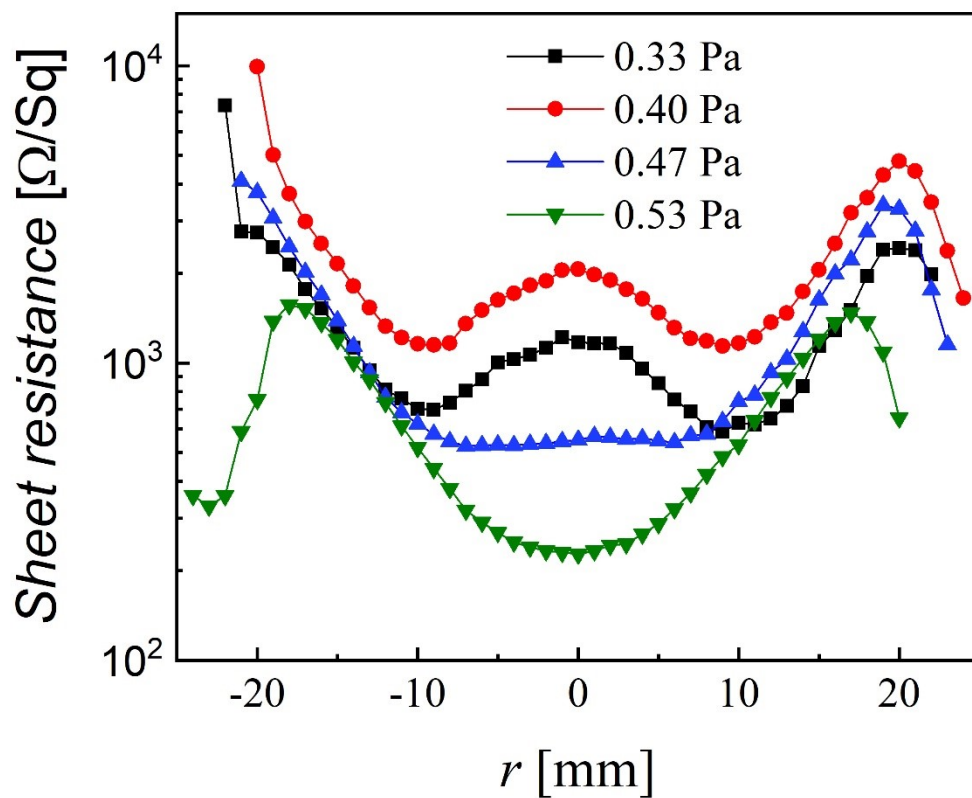


Fig. S2 Spatial distribution of the sheet resistance for different deposition pressures measured for 10x50 mm² samples. The 50x50 mm² samples deposited under similar conditions have been used to measure the 2D XRD profiles presented in Fig. 6.